

Multi-User Facilities in LNNano:
Electron and Scanning Probe Microscopies,
Micro/Nanofabrication

Fernando Galembeck
Director, LNNano/CNPEM



1st Workshop on Multi-User-Equipment and Facilities
04/06/2014

CNPEM

- Non-governmental, non-profit organization (organização social), operates the Synchrotron, Biosciences, Bioenergy (CTBE) and Nanotechnology National laboratories in Campinas, SP.
- Ruled by **legislation applicable to private organizations**
 - Procurement done following specific rules (“Regimento de Compras”), **not subject to Law 8.666.**
 - Employment is **ruled by CLT.**
- Institutional Development Plan completed in 2013, effective from 2014.
 - Directors report to the Board.
 - Career tracks: Researchers, Specialists, Technicians, Management.

CNPEM Mission

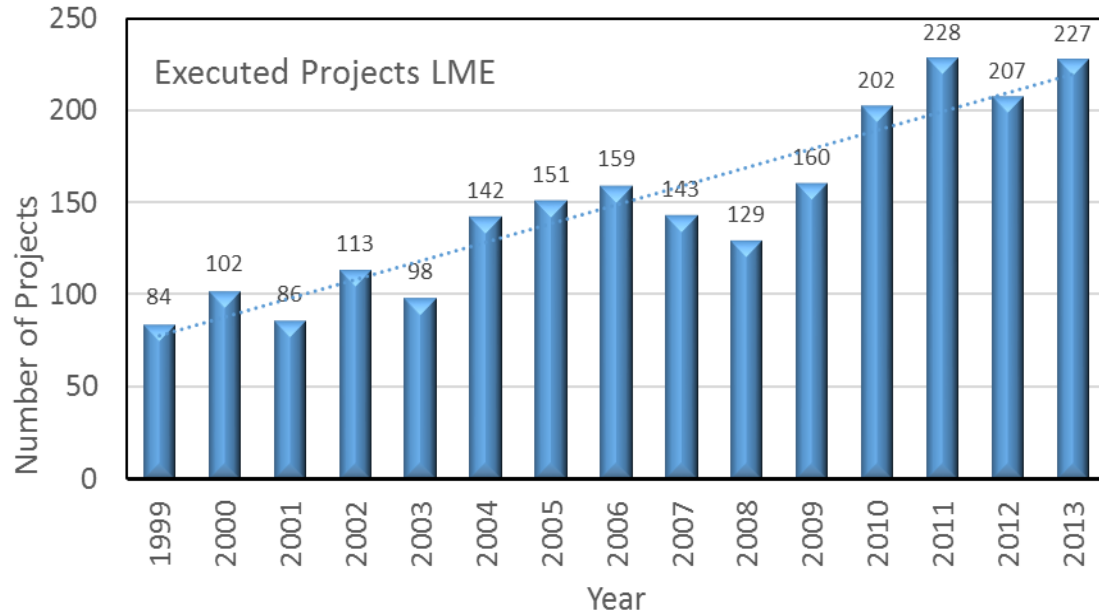
- Operation of national laboratories: **support to academic and R&D users**
 - **In house R&D**
 - Support to **innovative companies**
 - **Training** and education



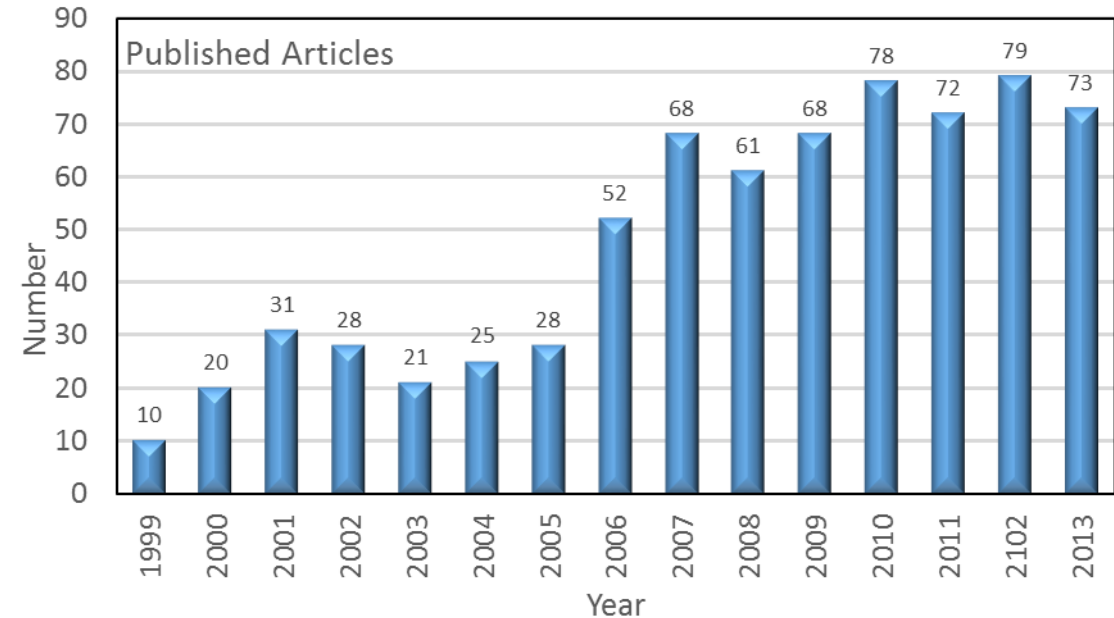
Funds for Electron Microscopy

- Multi-User Fapesp Project (Proc. 96/4241-5)
 - later expanded through another multi-user Project (Proc. 2002/04151-9).
- **No funds from the 2009 Fapesp call or later.**
- Equipment renewed with federal funds
 - Two SEM instruments allowing different configurations and experiments: FINEP (01.10.0561.00), 2011.
 - FIB (Dual-beam) instrument, 2014.
 - Annual service contracts for preventive maintenance (ca. R\$ 360K .2013).
 - Spare parts, consumables, training.

15 years working as an open, multi-user facility



Total: 2004 projects



714 published papers

- 88,548 hours of microscopy provided
- 1072 users trained
- 5 technicians trained for other centers
- 21 user companies (under fees)

The microscope agenda is saturated
Sessions booked *ca.* 4 weeks in advance

- In situ experiments (temperature, mechanical, electrochemical, gas...)
 - Atomic resolution
 - Diffraction
 - Spectroscopy (EELS, EDX)
 - Tomography
 - Cryomicroscopy
 - Single-particle (protein structure)
 - Holography



Staff - Materials Science

Dr. Jefferson Bettini, CNPEM researcher, > 15 years experience*

Dr. Erico Teixeira Neto, CNPEM researcher, > 8 years experience

Dr. Carlos Ospina, CNPEM researcher, > 7 years experience

Dr. Naga Vishnu, arriving from Ireland in July 2014, > 5 years experience

Sidnei Araujo, CNPEM technician, > 15 years experience*

Fabiano Montoro, CNPEM technician, > 3 years experience*

Other experts in LNNano: Antonio Ramirez, Cristiane Souza, Fernando Galembeck

* Participated from advanced training activities in 2013-2014.

Staff - Life Sciences

Professor Marin Van Heel, CNPq CsF Fellow, > 40 years experience (Imperial College, University of Leyden Cryomicroscopy Center), supported by CsF project

Dr. Rodrigo Portugal, CNPEM researcher > 10 years experience

Dr. Alexandre Cassago, CNPEM researcher, > 2 years experience

Education

V Theoretical-Practical Transmission Electronic Microscopy School (Jan 2014)

315 applicants, 85 participants. <http://lnnano.cnpem.br/temscool/>

Developing Advanced Expertise at LME/LNNano: planned events

Human resources - Materials Science

Dr. Jefferson Bettini – July 2015 – Oxford/UK – Prof. Angus Kirkland

Double corrected microscope – Amorphous materials - **Spectroscopy**

Dr. Erico Teixeira Neto – July 2016 – Lyngby/Denmark – Prof. Thomas W. Hansen

Environmental Transmission Microscope - Catalytic nanoparticles – **In-Situ**

Dr. Carlos Ospina – December 2014 UCLA – Prof. Jianwei (John) Miao

Corrected Microscope – Core-Shell Nanoparticles – **Tomography**

Dr. Naga Vishnu – hired from July 2014

December 2015 - Professor Rafal Dunin – Julich/Germany

Double corrected Microscope - Semiconductors Defects – **Holography**

To be selected – **Advanced Electron Diffraction**

Human resources - Life Sciences

Dr. Alexandre Cassago – July 2016 – Leyden – Prof. Marin van Heel

Macromolecular 3D reconstruction – **Single Particle Analysis**

To be selected – **Cryo-tomography**



TEM JEM 3010 - 15 years
EDS Capability, Resolution 1.7 Å



TEM JEM 2100F – 6 years
STEM, EDS and EELS
Resolution 1.9 Å



TEM JEOL JEM 2100 – 6 years
STEM, EDS
Resolution 2.4 Å

Shared between
Materials and Life
Sciences



SEM Inspect 50F – 2 years
STEM and EDS
Resolution 10 Å



SEM Quanta 650F – 2 years
EDS and EBSD
Resolution 10 Å



Dual Beam Helios 660 – 1 month
EDS3D and EBSD3D
Nanolitography, Ion and Electron
Beams, 6 Å res.

Other equipment

- JEOL LV SEM, largely used for service to companies and less demanding users.
- JEOL FESEM: 13 years old, currently used as a platform for instrumental development (from Fapesp).
- Equipment for sample preparation (cutting, polishing, ion-milling, ultramicrotomy, sputtering, evaporation...)

Physical infra-structure

- Double-walled building.
- Heavy concrete instrument beds.
- Air-conditioning through smooth dispersant tissue, no wind, strict temperature control.
- Sound absorbent inner wall lining.
- Problems as of 2011:
 - Elettromagnetic noise, solved by making two interventions using active noise suppressors (2011 and 2014).
 - Full dependence from grid power supply: budgeted for 2014 using funds from Finep.

Open, transparent user access



CNPEM
Centro Nacional de Pesquisa
em Energia e Materiais



Informe seu login e
acesse o Portal de
Usuários.

Você não possui login,
informe um e-mail e clique
no botão acessar.

E-mail

Senha

[Esqueci minha senha](#)

Portal de Usuários

O Portal de Usuários do CNPEM realiza a gestão das propostas de pesquisas submetidas pela comunidade de pesquisadores do Brasil e do exterior para uso das instalações científicas do LNLS, CTBE, LNBio e LNNano.

Todos os pesquisadores interessados em utilizar os equipamentos dos laboratórios do CNPEM devem utilizar o Portal de Usuários para submeter suas propostas de pesquisa e projetos científicos à aprovação dos laboratórios.

O Portal de Usuários permite ao pesquisador acompanhar, via Web e em tempo real, o status da sua proposta de pesquisa, garantindo a transparência de todo o processo de avaliação.

Ajuda



É recomendado desabilitar bloqueadores de pop-ups.

[Serviços de Apoio ao Usuário \(SAU\)](#)

Telefone: 55 019 3512-1021/ 1025

E-mail: sau@cnpem.br

Comitê de Usuários do LNLS

comite.usuarios@lnls.br

Gestão do desenvolvimento tecnológico:

Grupo de Tecnologia de Informação e Comunicação - TIC

Recomendado



Attention to users

- Available time, support to users and user output assessed every three months by the CNPEM Board and every six months by a committee nominated by MCTI (Comissão de Avaliação do Contrato de Gestão).
- Complaints and suggestions can be sent to the Electron Microscopy Facility Manager, to the Director of LNNano, to CNPEM General Director and to the CNPEM ombudsman.
- **Most recent complaint received in 2011.**
 - A user sent a message to the Scientific Director of Fapesp suggesting that São Paulo state researchers should use at least 50% of TEM equipment time. Then, he was informed that São Paulo state researchers (not including CNPEM personnel) were using 80% TEM time.

LME Assessment from the LNNano International Advisory Board

Adalberto Fazzio – IFUSP, USP (Brazil)

Brian Vincent – University of Bristol (Inglaterra)

Daniel Lacks – Case Western Reserve University, Cleveland OH (EUA).

Ponisseril Somasundaran – Columbia University, New York (EUA).

Markus Antonietti – Max Planck Institut, Golm (Alemanha).

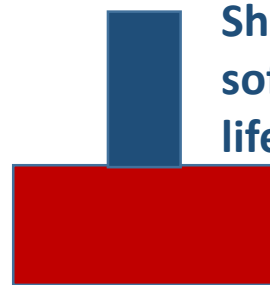
Oswaldo Luiz Alves – IQ, Unicamp (Brazil)

*This group has established a **truly world-class facility**. In addition to more standard instruments, this group operates a cryo-TEM, which **opens up the exploration of biomaterials and other soft-materials**. We note that electron microscopy is rather expensive -both to purchase as well as to maintain and operate. For this reason, it is most efficient to **concentrate resources to develop one strong facility in Brazil rather than several weaker ones**. In this context, the **LNNano group is poised to take a leadership role throughout Brazil and South America**. One way to help achieve this goal may be to **create satellite locations with remote instrument access**, which are nearer to other users but are run by LNNano staff”.*

Acquisitions under negotiation in 2014



Double Corrected TEM - Holography
STEM, EDS and EELS, In-situ
Tomography, Resolution 1.0 Å

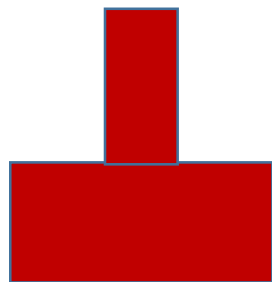


TEM 120 kV
EDS - Cryo
Resolution 3.2 Å

Shared between
soft materials and
life sciences

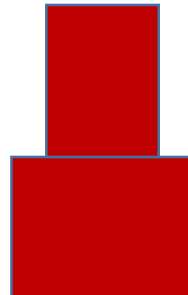


Dual Beam
Dedicated to sample
preparation
Resolution 10 Å



TEM 200-300 kV – Energy
Filter, Phase Plate, Direct
Detector, Resolution ~ 2 Å

~ 2 years

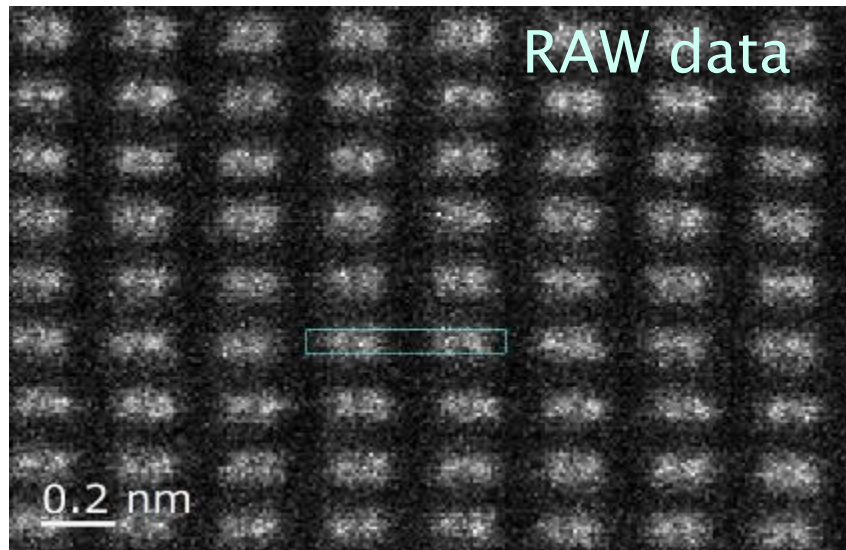


Dual Beam – 3D Reconstruction
Dedicated to Life Sciences
Resolution 10 Å

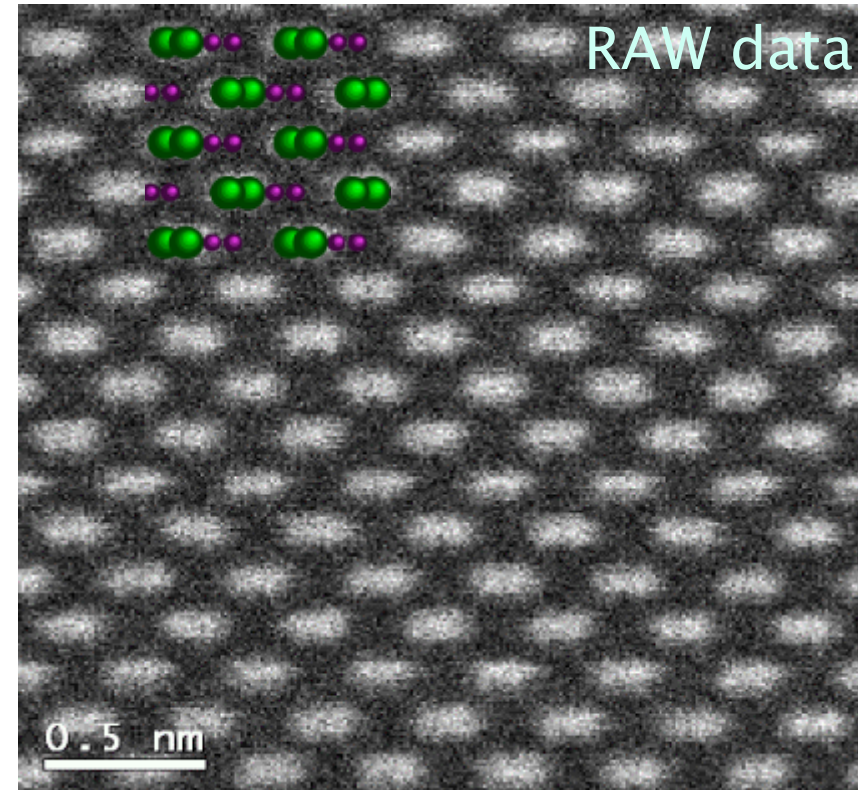
Currently there are three
corrected instruments in
Brazil, none in São Paulo
state.

Why a corrected electron microscope?

Resolution



Si(112) 78 pm dumbbell image

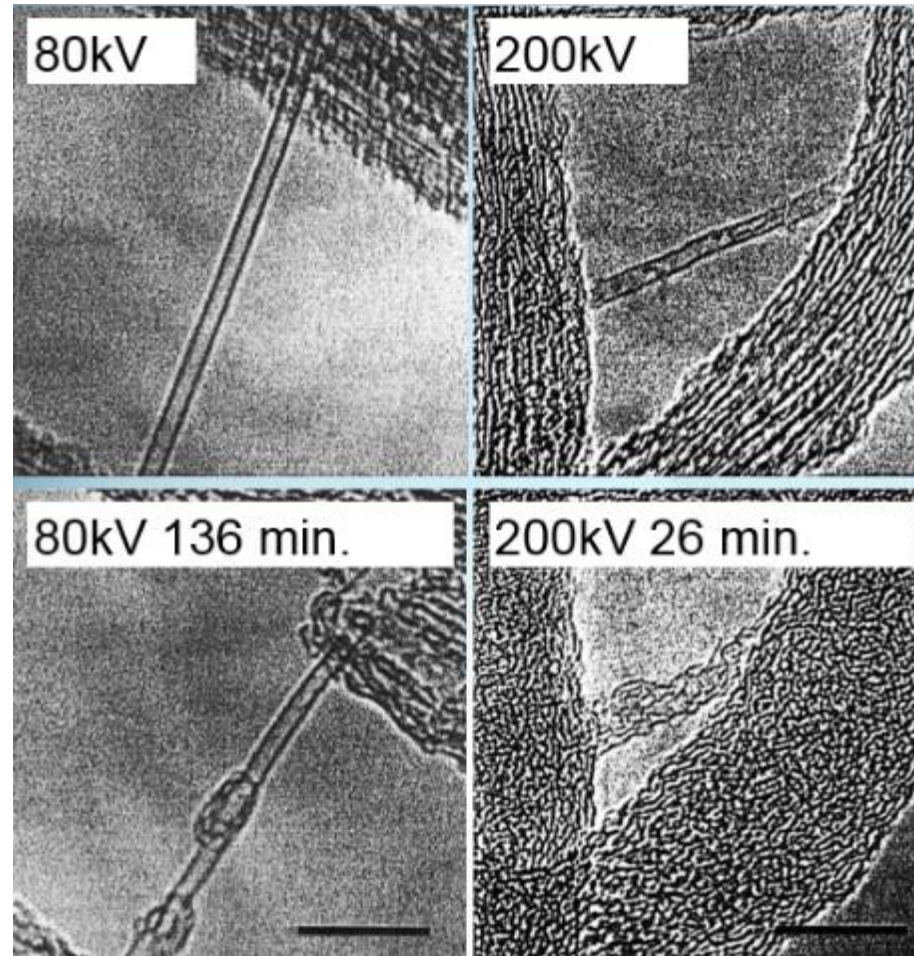
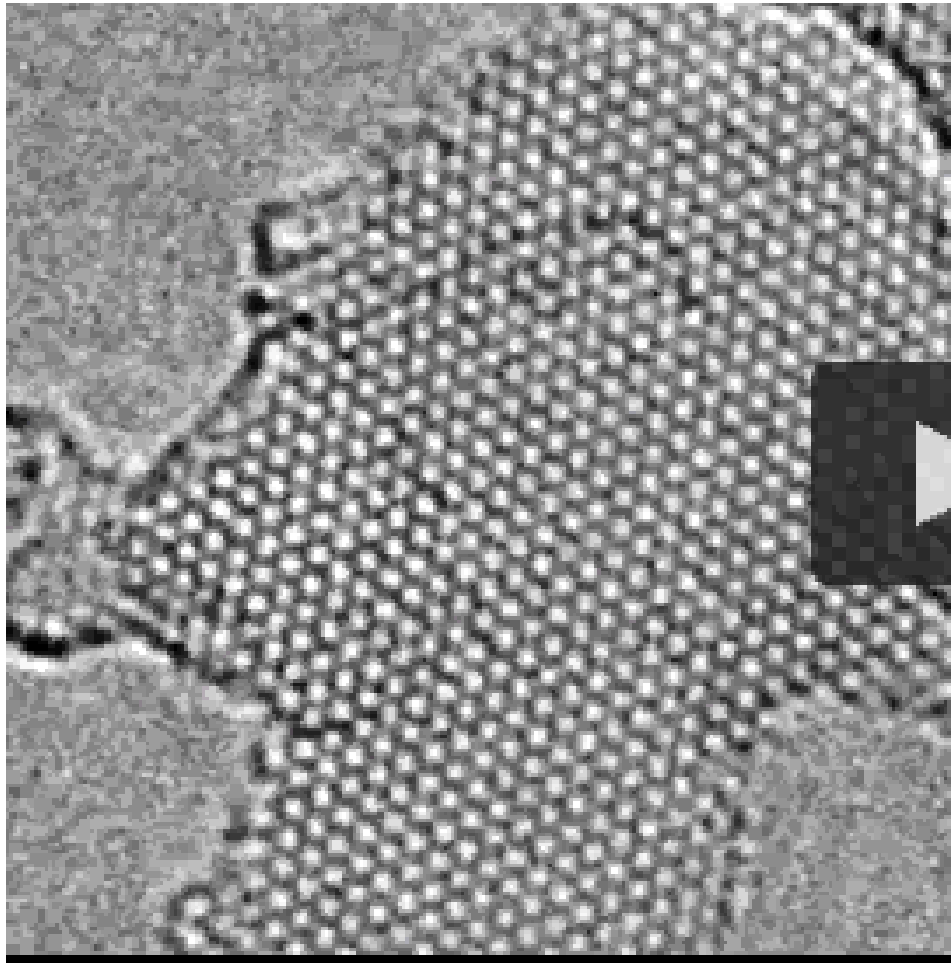


GaN [211] 63 pm HAADF at 200 kV

Resolution below 1.5 \AA can be reached automatically.
Atomic resolution (below 1 \AA) can be achieved in STEM and TEM.

Why a corrected electron microscope?

Light Materials

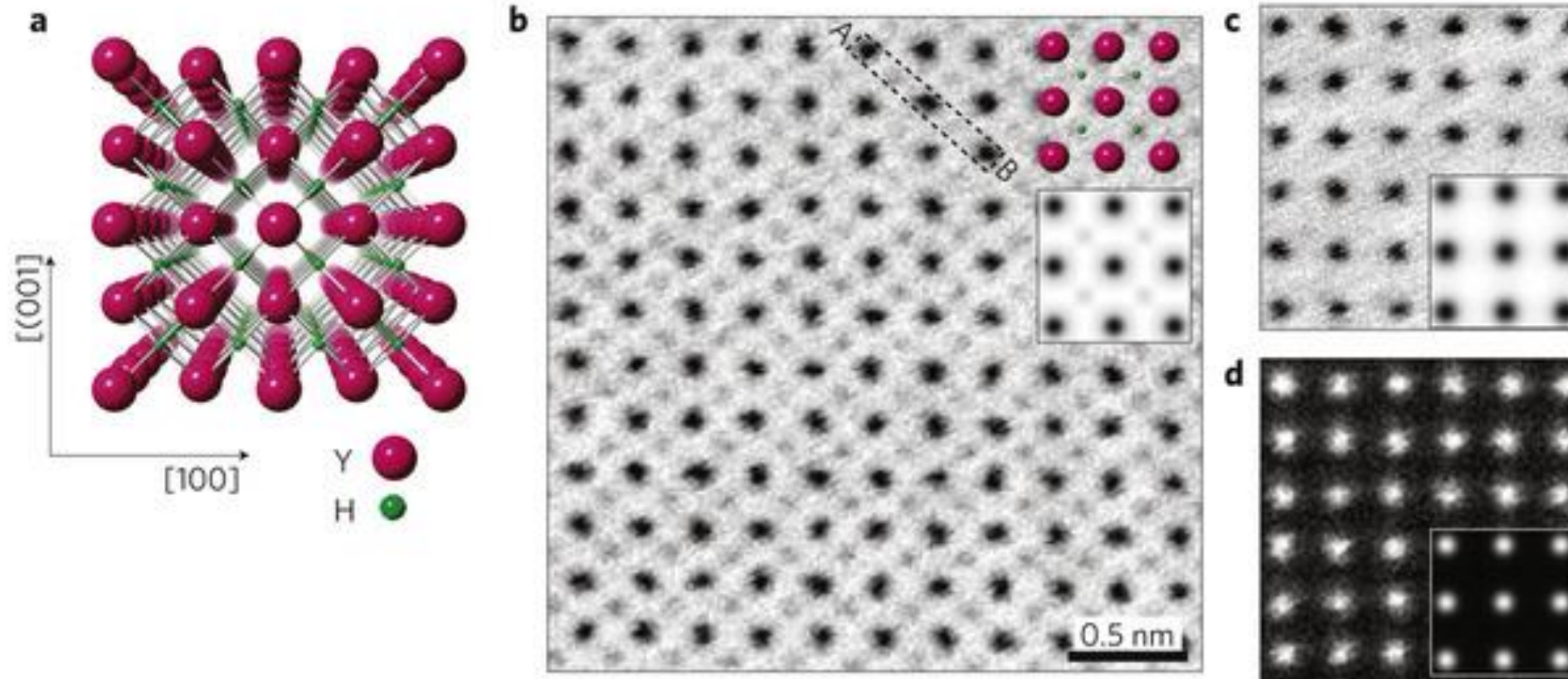


Knock-on damage is reduced at low acceleration voltage.

Transformation of a graphene sheet into a fullerene.
Video credit: Andrey Chuvilin, et al.

Why a corrected electron microscope?

Light Materials



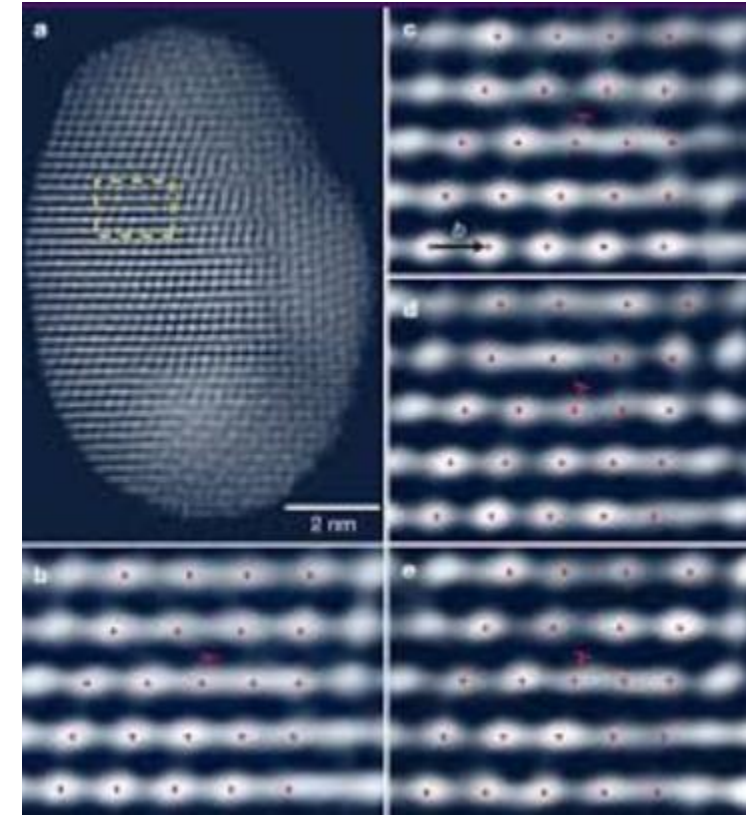
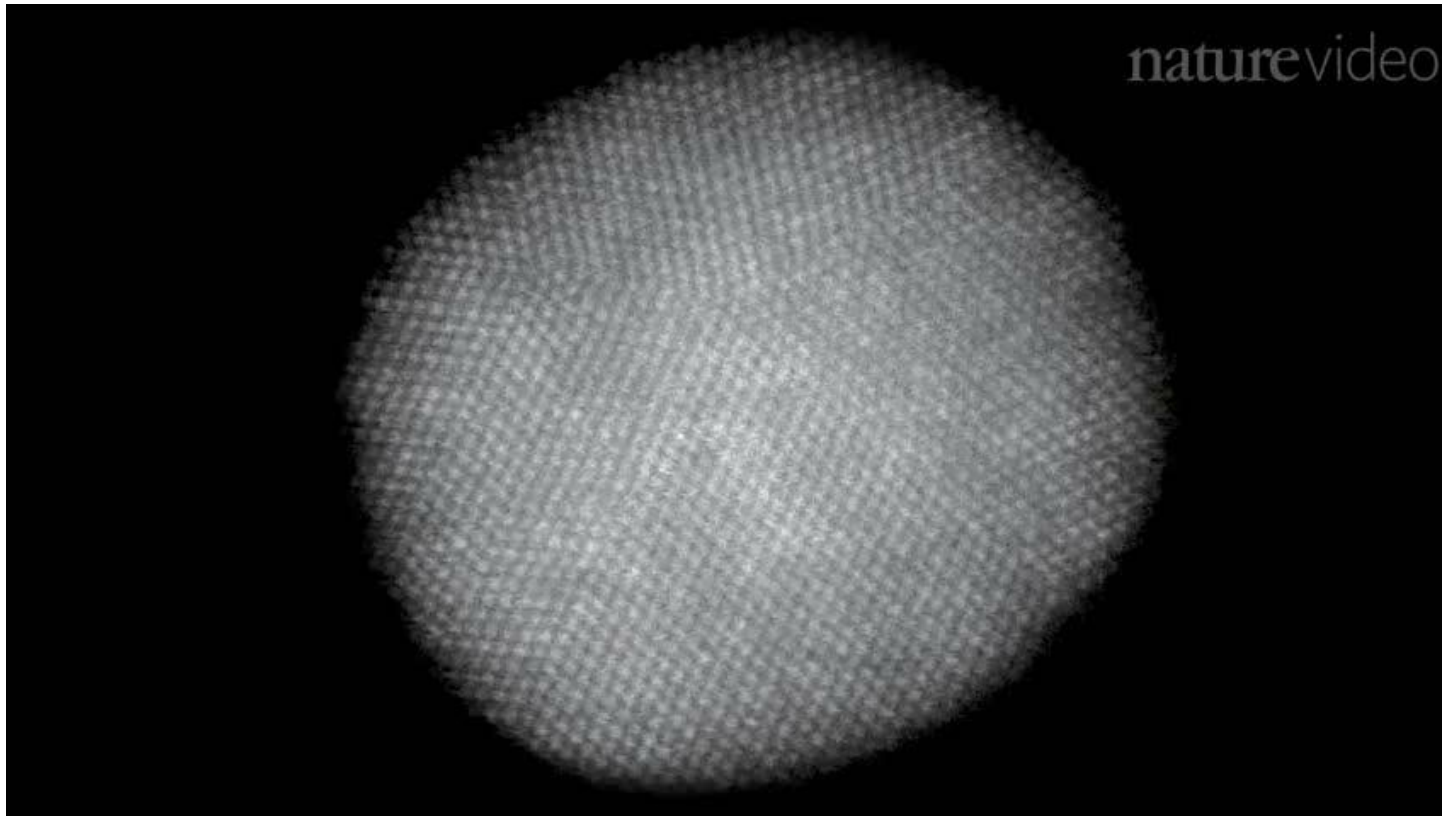
Direct imaging of hydrogen-atom columns in a crystal by annular bright-field electron microscopy

Ryo Ishikawa, Eiji Okunishi, Hidetaka Sawada, Yukihiro Kondo, Fumio Hosokawa & Eiji Abe

Nature Materials 10, 278–281 (2011) doi:10.1038/nmat2957

Why a corrected electron microscope?

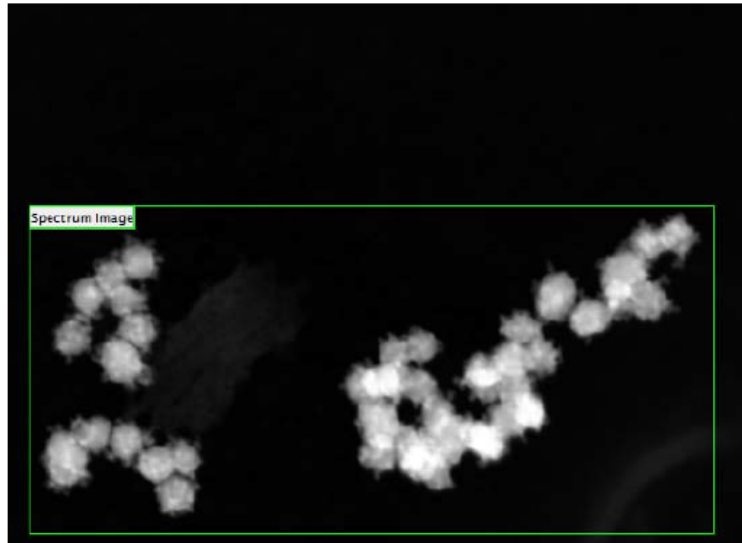
High Resolution Tomography



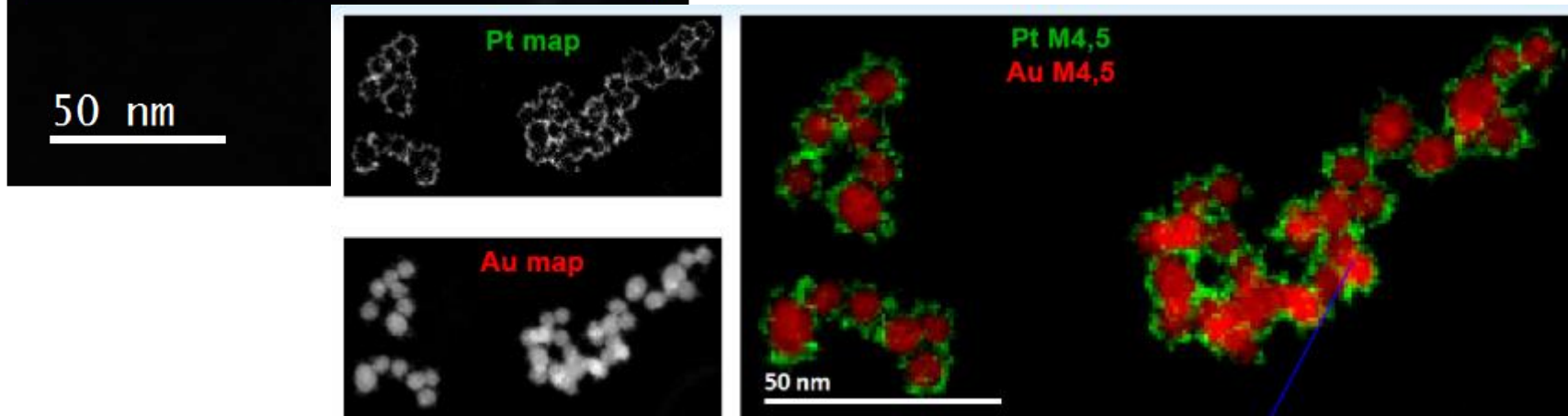
Chen, C. C. , Zhu, C., White, E. R., Chiu, C. - Y., Scott, M. C., Regan, B. C., Marks, L. D., Huang , Y. & Miao, J. Three - dimensional imaging of dislocations in a nanoparticle at atomic resolution. **Nature** 496 , 74 – 77 (2013).

Why a corrected electron microscope?

Data throughput



- Analysis carried out at 200kV
- EELS High-Loss 1100eV – 3100eV: 5ms
- Dataset size: 198 x 95
- CA: 19.9mrad
- Collection angle: 35mrad
- The green box is the area where the beam was scanned during the acquisition of the EELS SI
- **Analysis carried out in about 110seconds**

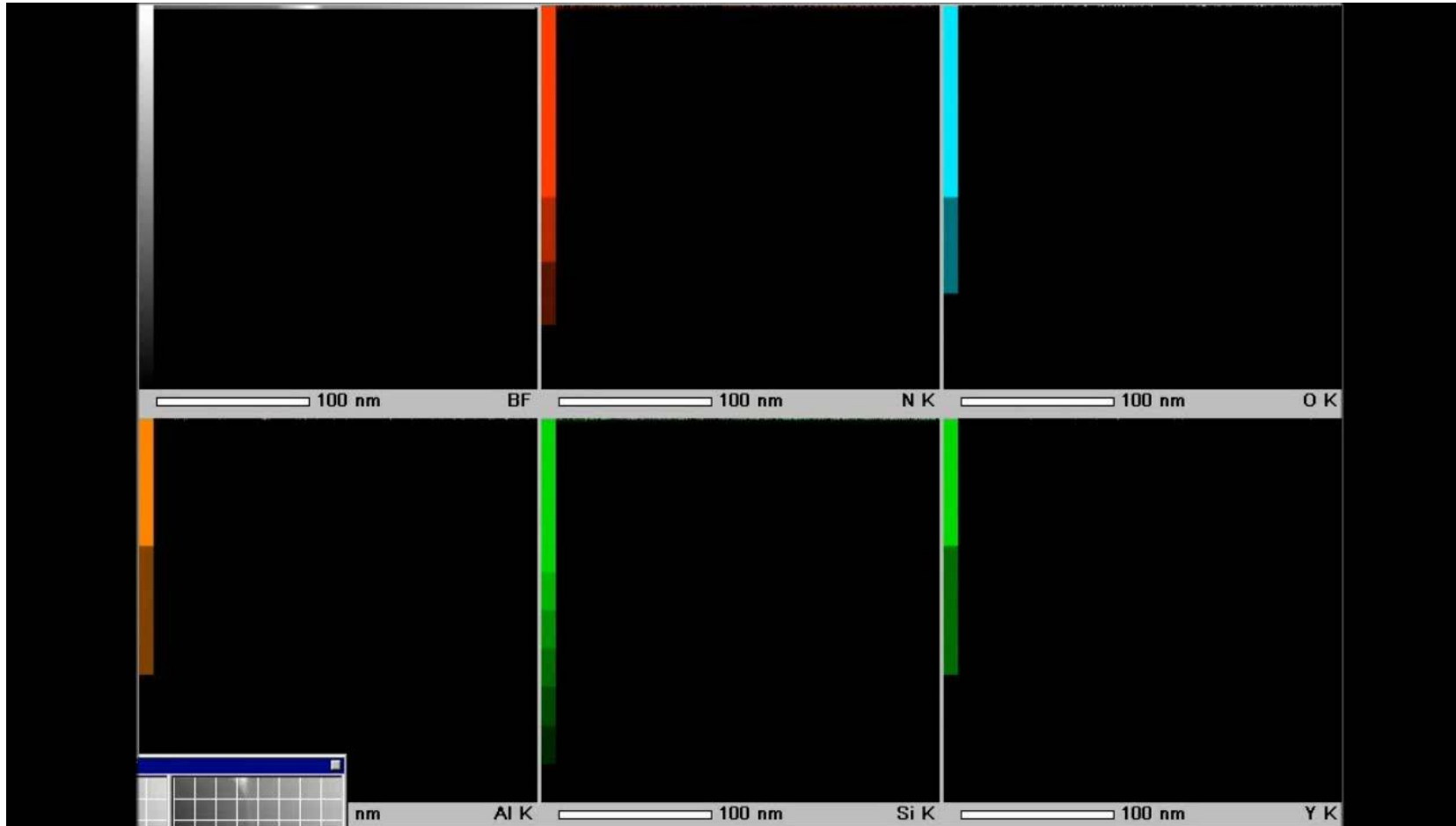


Corrected microscope reaches 6X higher current at the same probe size. New detectors are 6X more efficient than our current ones.

Twice as many users can attended

Why a corrected electron microscope?

High data throughput



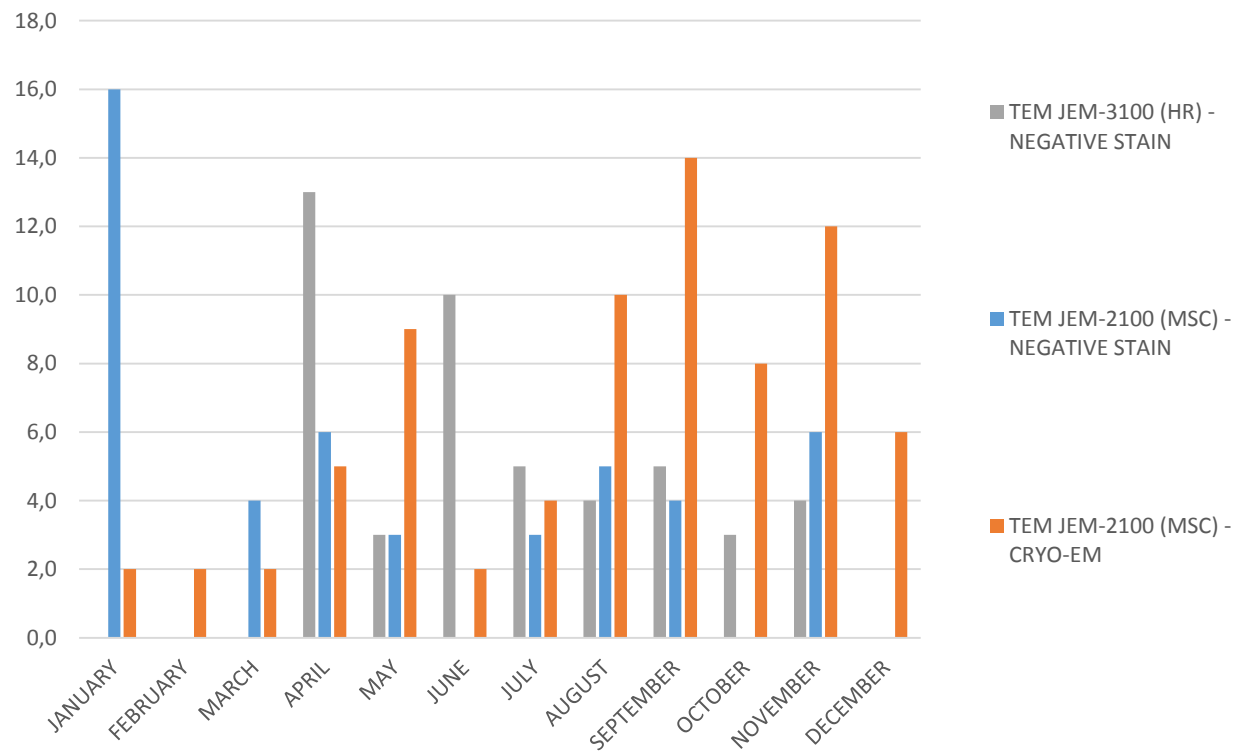
Faster results

256x256 pixel
Real time display

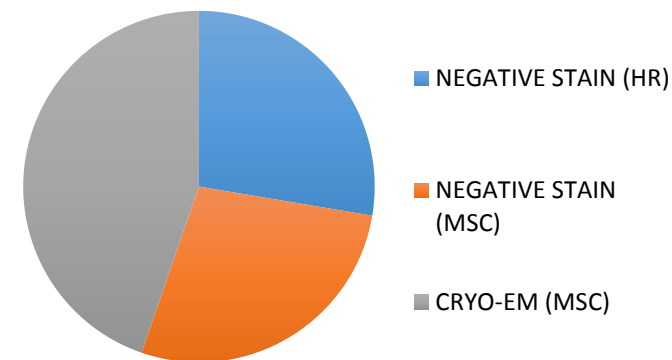
High-Speed, EDS STEM-SI Acquisition: Nitrogen, Oxygen, Aluminum, Silicon and Yttrium

Why a electron microscopy facility for Life Sciences?

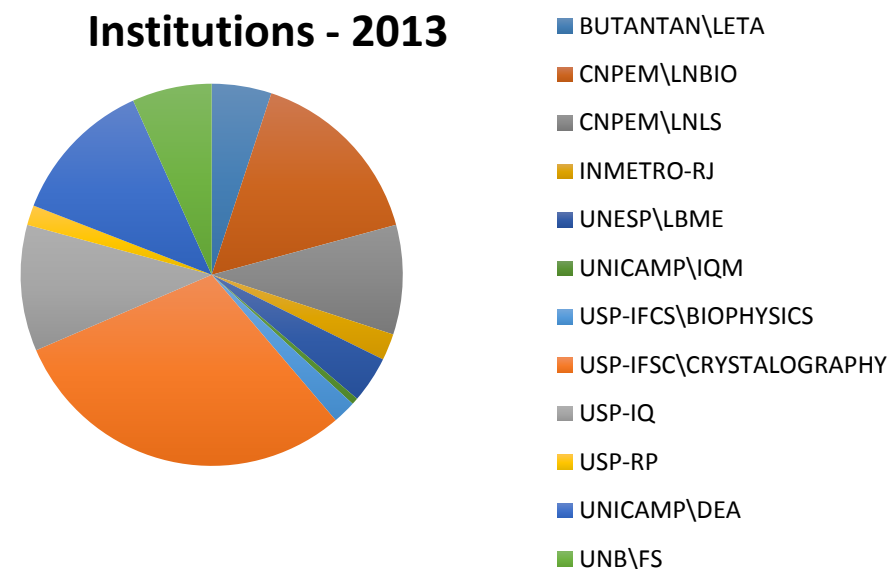
Allocated Shifts (1/2 day) – 2013
(including use during weekends)



Sample Preparation and Equipment - 2013

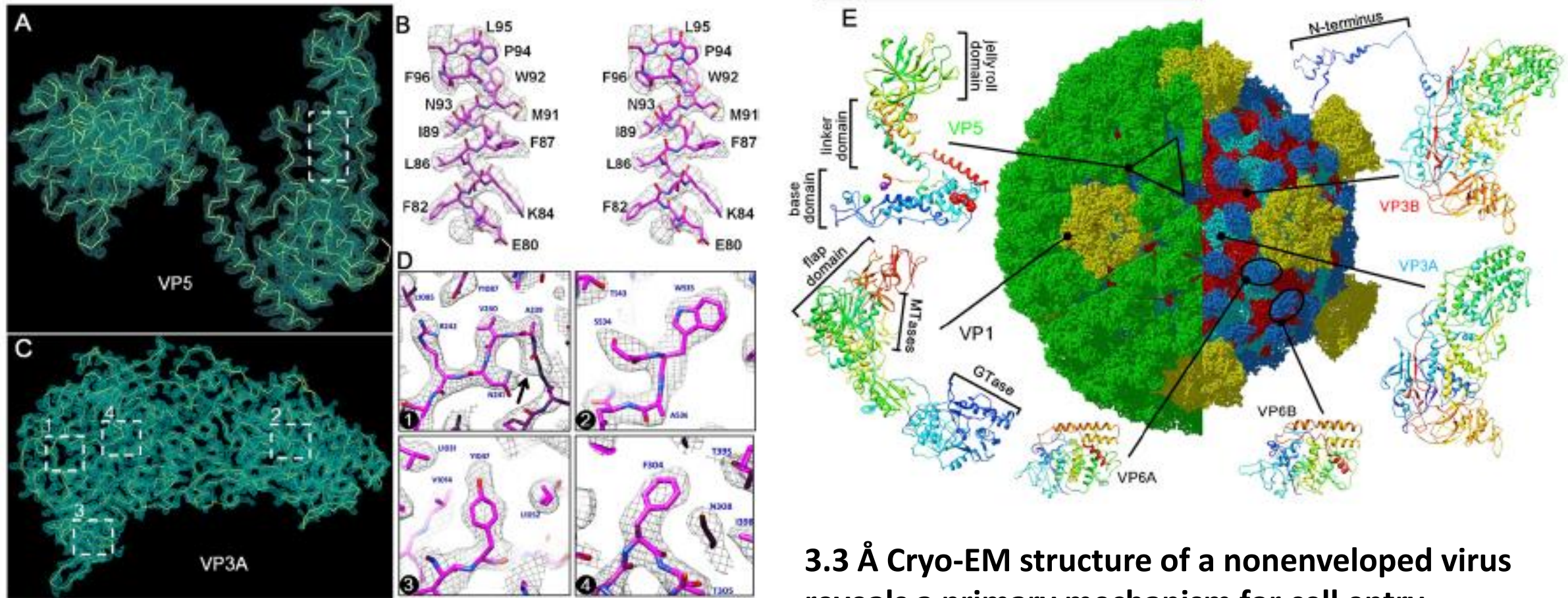


Institutions - 2013



Why a high end cryo electron microscope?

3D structure of macromolecules at near atomic resolution



3.3 Å Cryo-EM structure of a nonenveloped virus reveals a primary mechanism for cell entry

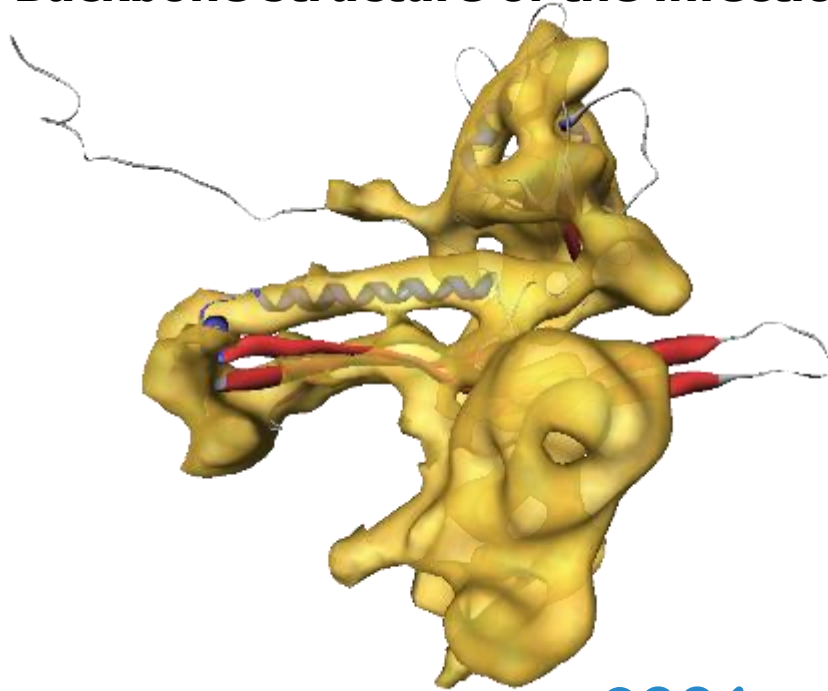
Reference

Zhang X., et al., (2010) *Cell*, 141:472-482.

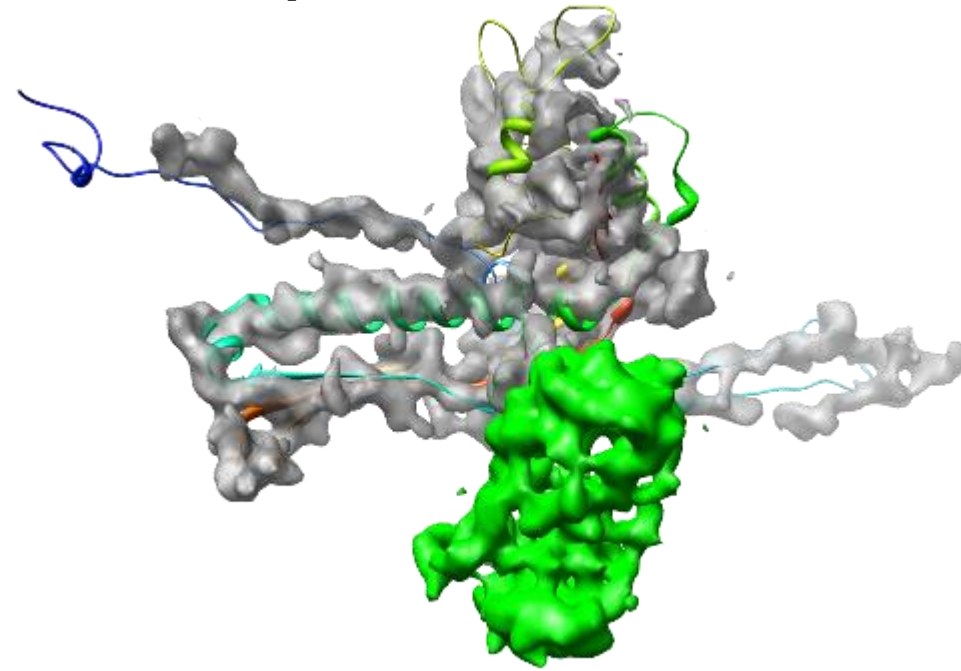
Why a high end cryo electron microscope?

3D structure of macromolecules at near atomic resolution

Backbone structure of the infectious ε15 virus capsid



9.5 Å 2006
(Nature)



4.5 Å 2008
(Nature)

Reference

Jiang et al., (2008), *Nature*, 451:1130. Backbone structure of the infectious ε15 virus capsid revealed by electron cryomicroscopy



LNNANO

Laboratório Nacional
de Nanotecnologia



Surface Science Laboratory – LCS
<http://lnnano.cnpem.br/laboratories/mta/>

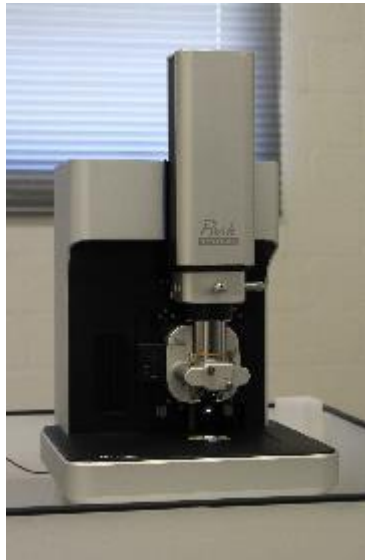


CNPem
Centro Nacional de Pesquisa
em Energia e Materiais

Ministério da
Ciência, Tecnologia
e Inovação



Scanning Probe Instruments



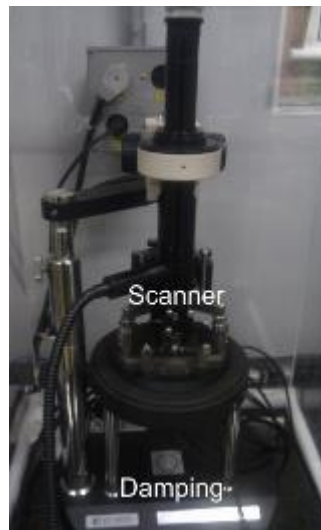
PARK – NX 10
Out. de 2013



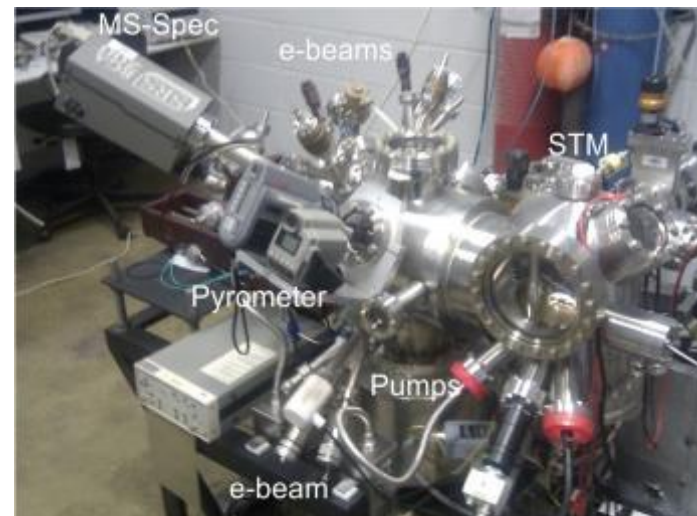
DIGITAL – Nanoscope IIIa



NANOSURF - FlexAFM



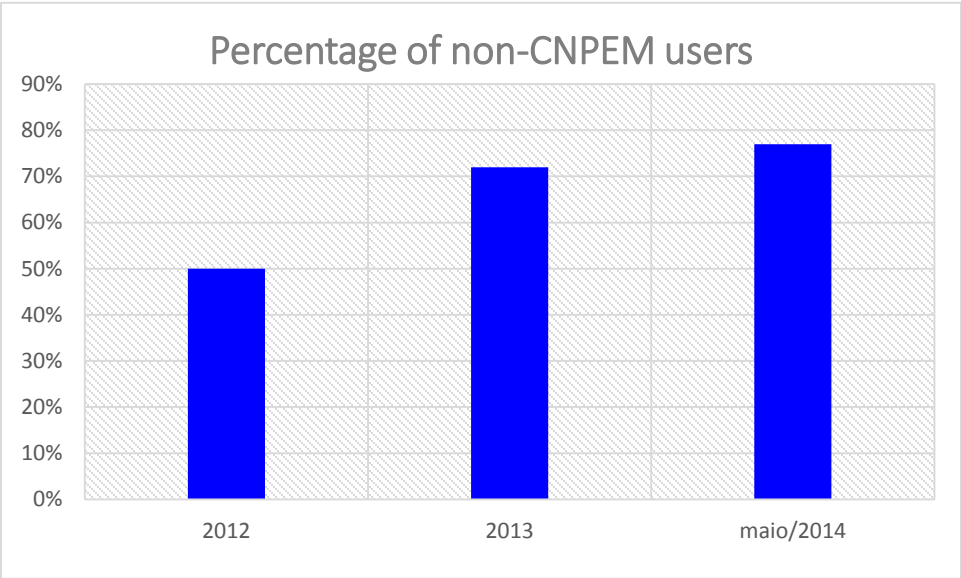
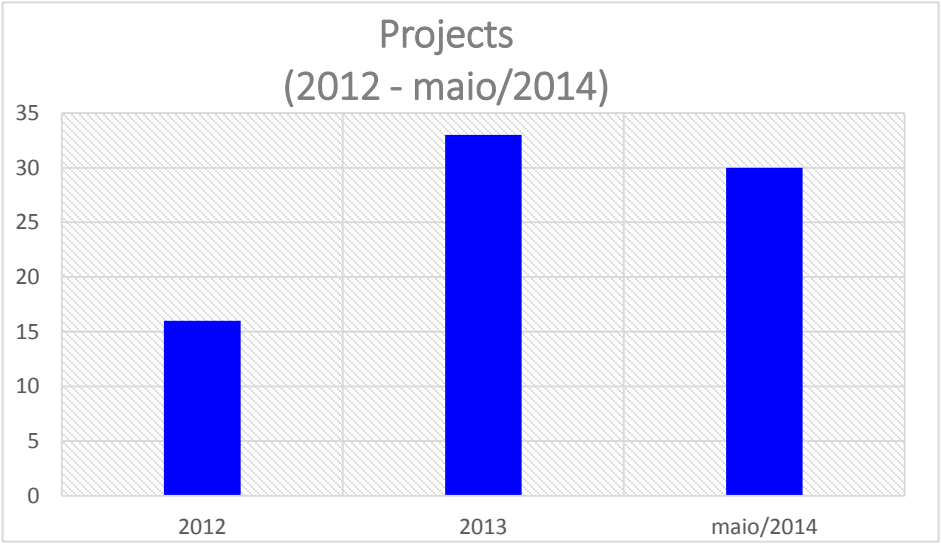
NT-MDT – Solver Pro



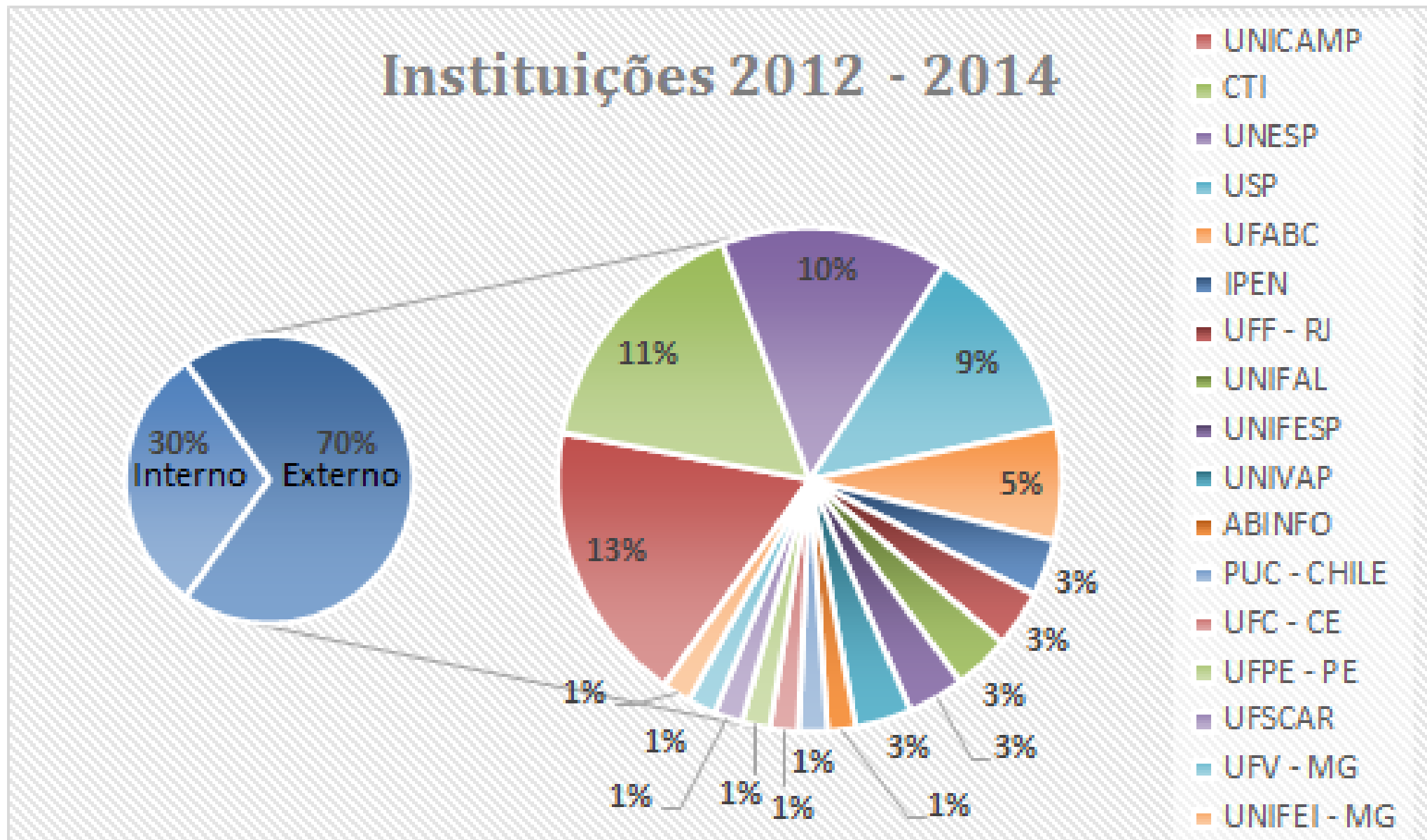
OMICRON – UHV-STM

Less expensive than electron microscopes but can only be **fully exploited** by a highly experienced team.

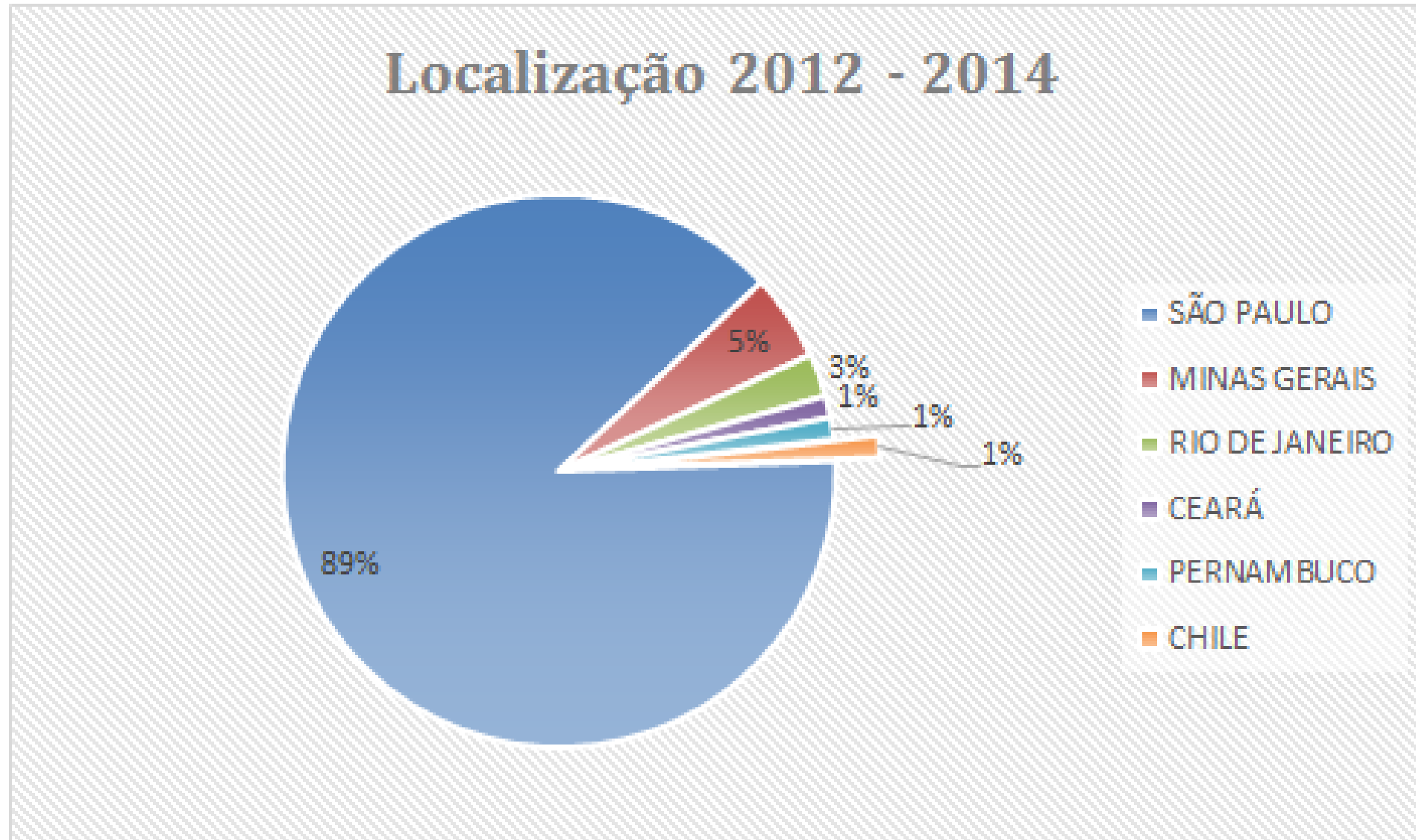
Users: 2012 – May 2014



User affiliation



User location





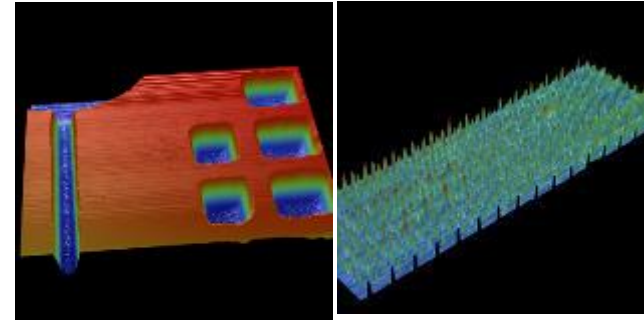
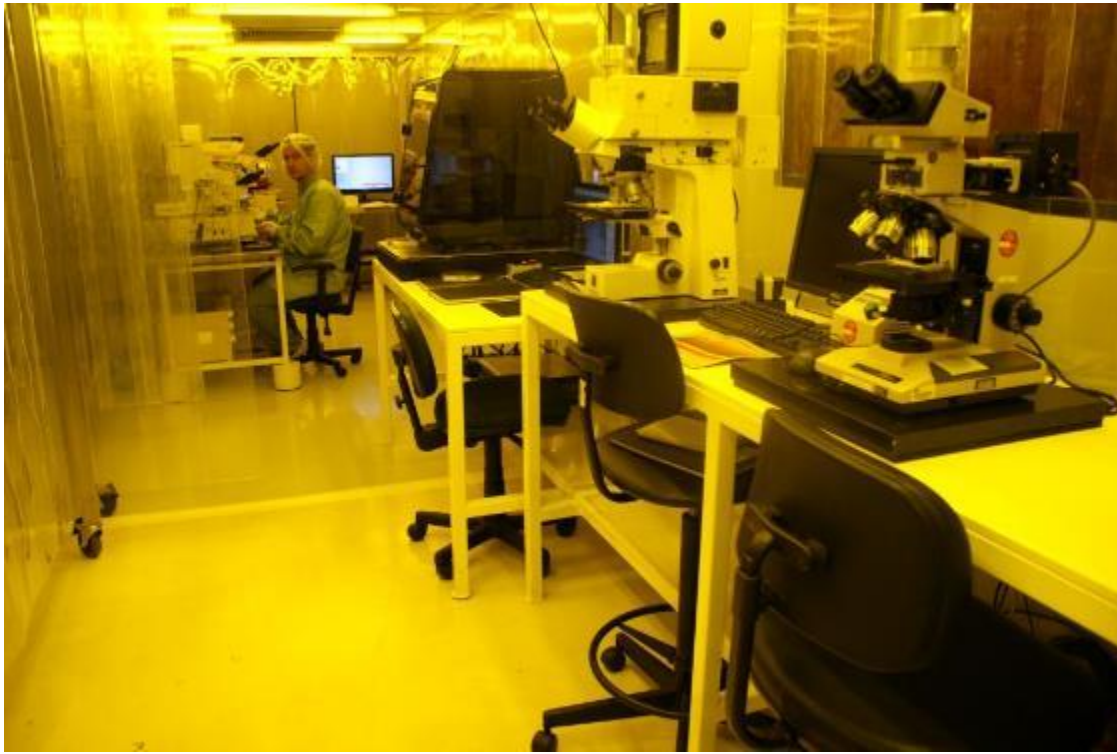
Micro/Nanofabrication – LMF
<http://Innano.cnpem.br/laboratories/lmf/>



Ministério da
Ciência, Tecnologia
e Inovação



LMF – Clean Room

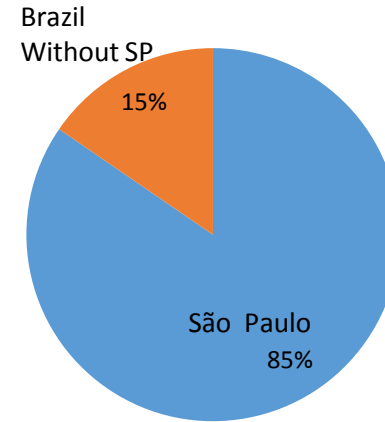
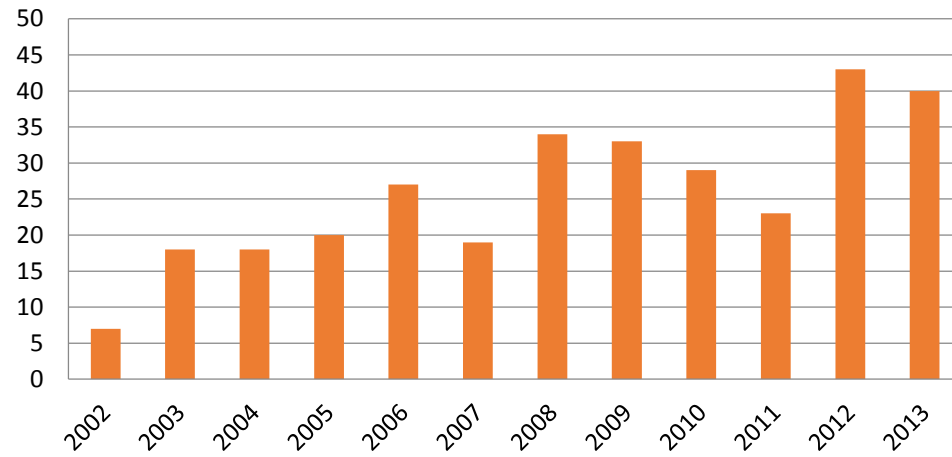


ISO 7 - 20m²

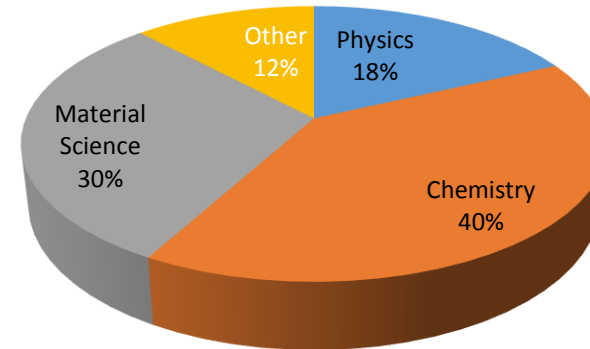
2 Karl Suss photoalignment units
Laser Pattern Generator(3 μ m)
Profilometer Dektak 150

User data

LMF- External Projects

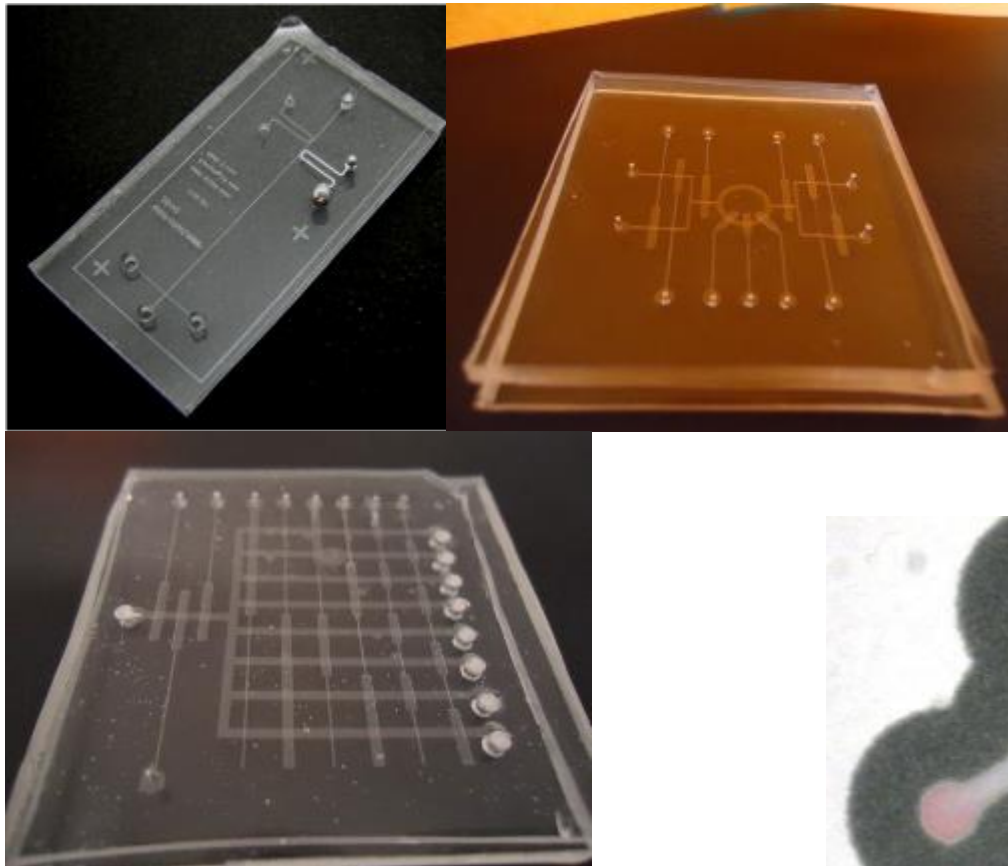


Year	Articles	Int. Conferences	Master Thesis	PhD thesis
2010	12	9	3	2
2011	10	4	2	1
2012	17	19	2	1
2013	23	18	6	3



Microfluidics platform

PDMS



Papel



Output

Water/etanol sensor

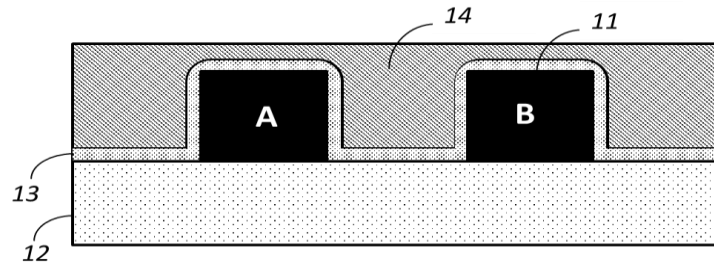
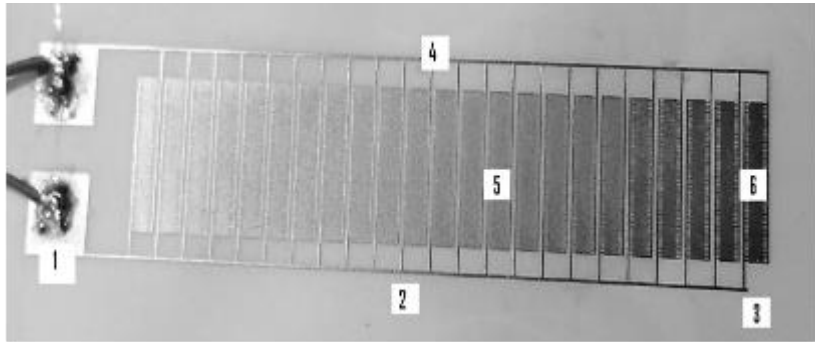


Figura 06

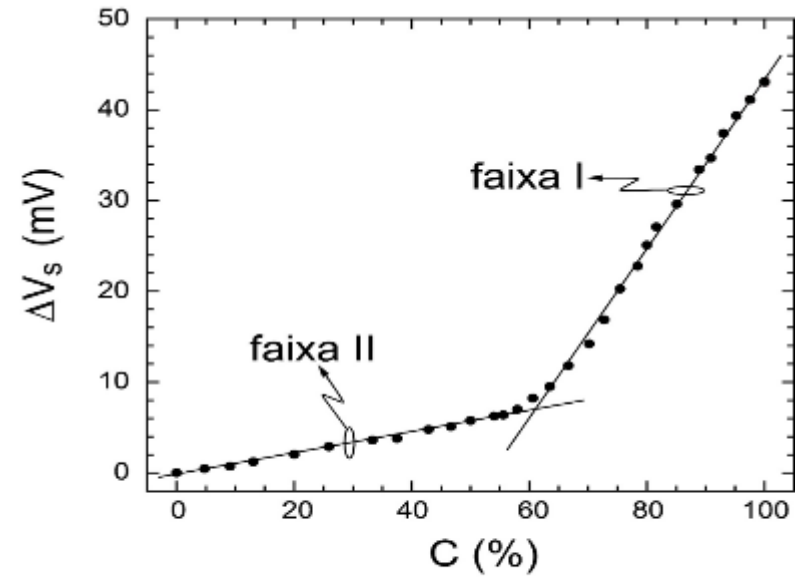
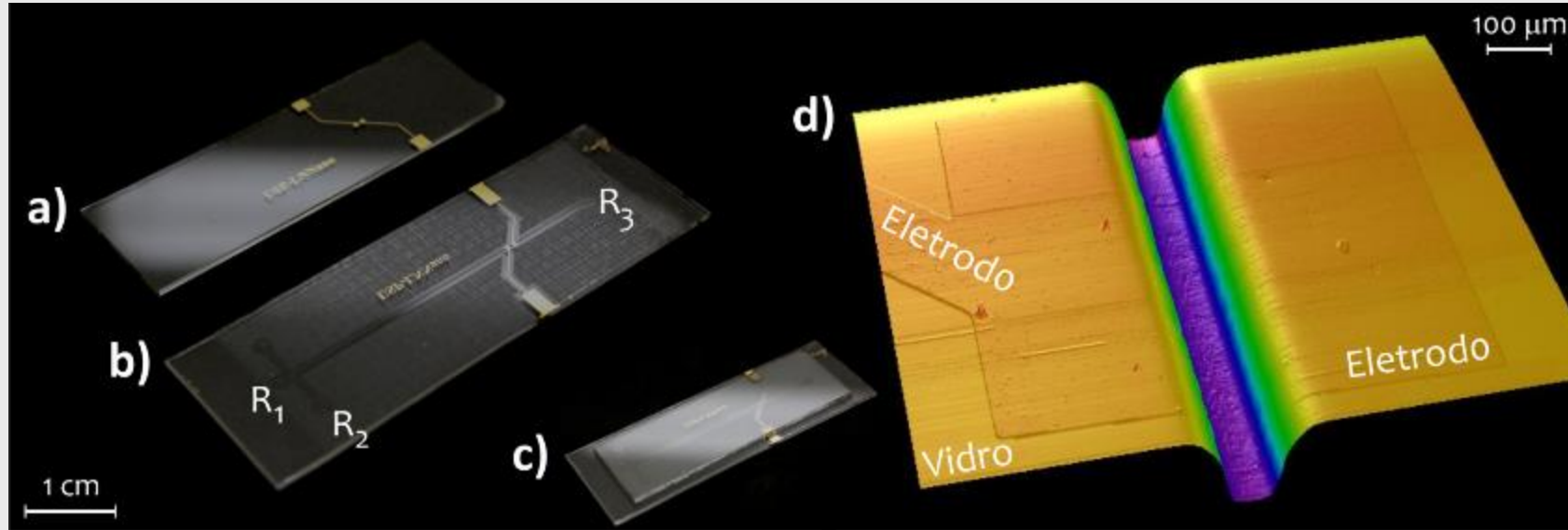


Figura 07

Output

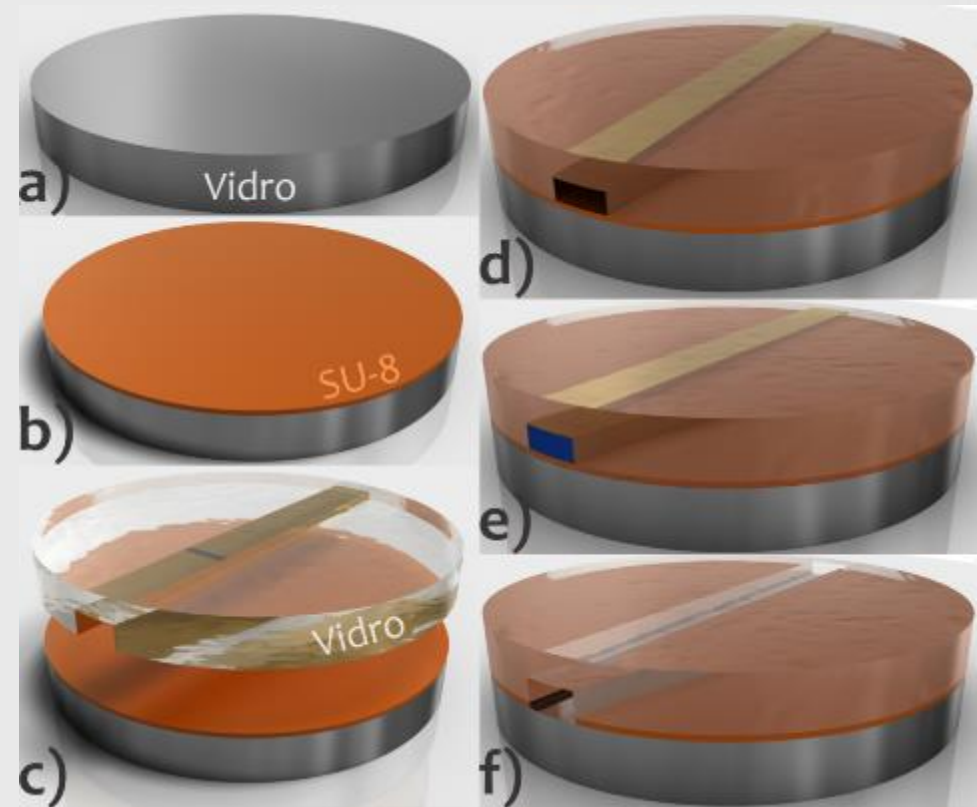
Concentric electrodes for C⁴D applications



- ✓ Detection limit is four orders of magnitude than using conventional planar electrodes.
- ✓ Patent (USP/SC & CNPEM), paper in *Chemical Communications*.

Sacrificial adhesive sealing for glass microchips

- ✓ **Simple, fast process** without using higher temperatures or pressure. Does not require clean room facilities.
- ✓ **Strong adhesion.** Microchannels support $p > 4$ Mpa.
- ✓ Patent Appl. (CNPEM e USP) **BR 102014012630-9**



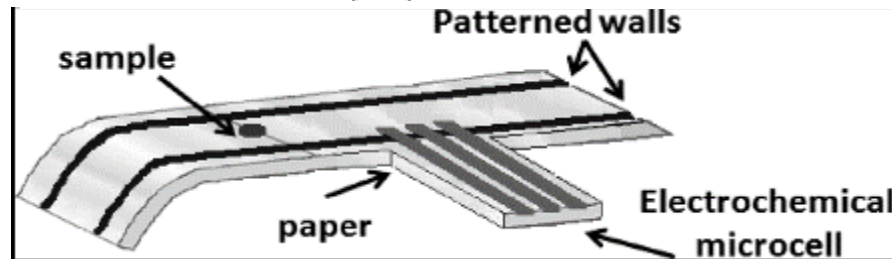
Output

Electrochemical Detection in a Paper-Based Separation Device UNICAMP and LMF/LNNANO

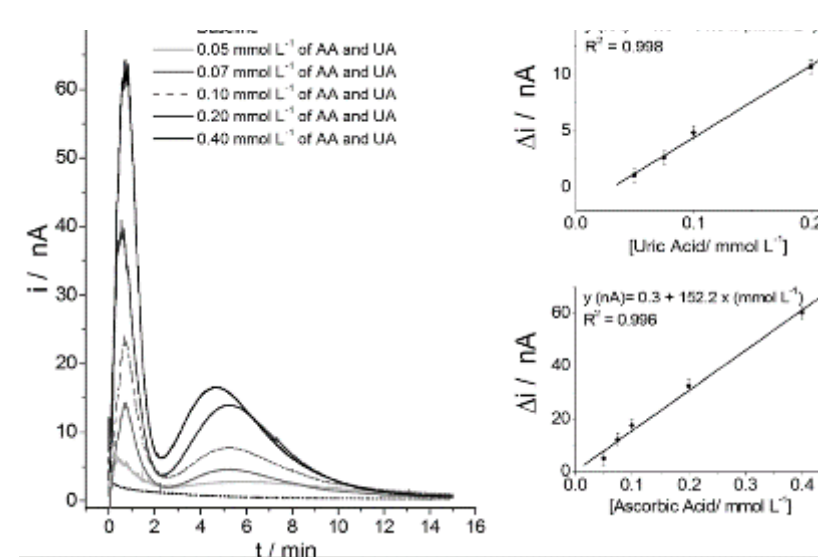
Analysis of salicylate concentrations in spiked blood samples.

Blood samples	Initial salicylate concentration/ mmol L^{-1}	Added salicylate concentration/ mmol L^{-1}	Biosensor recovery/%	Experimental salicylate concentration ^a / mmol L^{-1}	
				Biosensor	Standard method
1	0.00	0.10	101.9	0.10 ± 0.01	-
2	0.00	0.25	109.1	0.28 ± 0.04	0.26 ± 0.06
3	0.00	0.51	100.6	0.51 ± 0.08	0.51 ± 0.05
4	0.00	1.01	119.3	1.21 ± 0.05	-
5	0.00	2.02	99.4	2.01 ± 0.06	2.02 ± 0.04

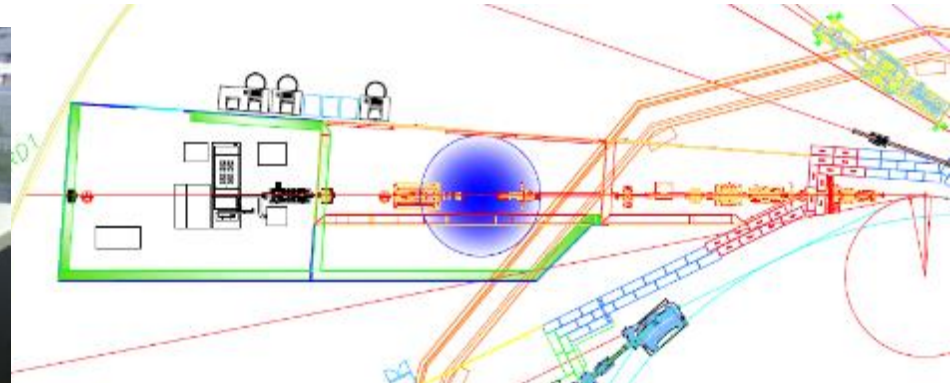
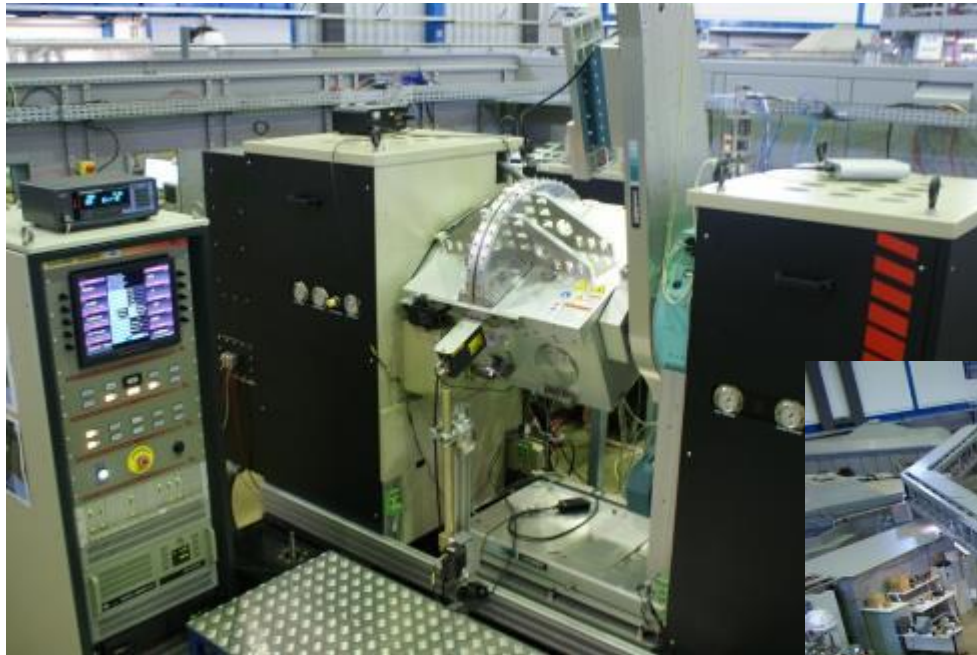
^a Mean \pm standard deviation ($n = 3$).



Patent Appl. Unicamp-CNPEM
PI 1011116-6 A2



Parallel Diffraction and Thermo-Mechanical Simulation



First Class User Community

Brazil, EUA, Germany, Japan,
Argentina, Peru,.....

Funded by Petrobras - FINEP

XTMS Users

Year/ Sem.	Institution Submitting	Origin Countries	Submitted projects	% Approval	Beam time [h]	Beam time for Brazilian Groups	Phase Transformation studies
2013/1	OSU- UNT-UNICAMP; OSU- UT-ORNL, ITA, CNEA	USA, Brazil, Argentina	4	100%	552	35%	Ti-As, SSs, DSSs, Ni- BAs, Steels, SMAs
2013/2	UT-ORNL, ITA, UFC, BAM, LNNano, USP	USA, Brazil, Germany	7	86%	960	58%	SSs, Ni-BAs, Maraging Steels, Adv. low distortion steels, DSSs, Super- Martensitic SSs.
2014/1	UT-ORNL, ITA, UFC, IBARAKI U., LNNano, USP, US-NAVY, UNICAMP, BAM, PETROBRAS	USA, Brazil, Japan, Germany	13	62%	984	59%	SSs, Ni-BAs, Maraging Steels, Ultra-high strength steels, Super-Martensitic SSs, Trip Steels, 9Ni Steels
2014/2	UT-ORNL, ITA, UFC, LNNano, USP, UNILIBoa, ORNL, U. BUENOS AIRES, PETROBRAS	USA, Brazil, Portugal, Argentina	13	46%	936	62%	SSs, Ni-BAs, Ultra- high strength steels, Trip Steels, 9Ni Steels, Pipeline steels.
Total		6	37	65%	3432	55%	

Ti-As: Ti-alloys; SSs: Stainless steels; DSSs: Duplex Stainless Steels;
Ni-Bas: Ni-based alloys; SMAs: Shape Memory Alloys

In-situ Measurements - XTMS

- Fundamental studies
 - Solid state phase transformations
 - Solidification
 - Solid-gas reactions (oxidation, etc...)
- Study strain/stress effect on phase transformations and vice versa
- Expedite new materials development
- Materials and processes optimization

LMF

- **O Laboratório de Microfabricação (LMF) do LNNano/CNPEM é um laboratório aberto, multidisciplinar dedicado ao desenvolvimento de dispositivos e processos em escala micro.**
 - fabricação de dispositivos semicondutores
 - sistemas microeletromecânicos (MEMS) (atuadores, engrenagens)
 - microfluídica (lab on a chip, soft lithography)
 - sensores ópticos
 - sensores químicos (colorímetros, separação, detecção – amperométrico e voltamétrico)
 - Sensores de deslocamento (MEMS acelerômetros)
 - Dispositivos RF (filtros THz, SAW, RFID)

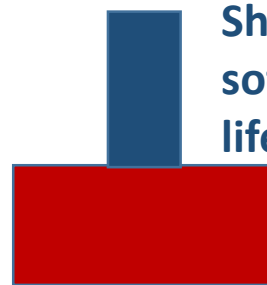
LMF

- O LMF oferece uma ampla capacidade de processamento.
- - Processos de fotolitografia (UV e laser patern generator)
 - Processos de corrosão por via úmida ou seca (metais, semicondutores, dieletricos e polímeros)
 - Physical Vapor Deposition (evaporação por feixe de elétrons e por sputtering DC/RF)
 - Chemical Vapor Deposition (PECVD de óxidos e nitretos)
 - Recozimento e cura (fornos térmicos e de tratamento rápido)
 - Inspeção (microscópios ópticos e imagem 3D)
 - Metrologia em filmes finos (medidores de espessura, elipsometria e resistividade)

Acquisitions under negotiation in 2014



Double Corrected TEM - Holography
STEM, EDS and EELS, In-situ
Tomography, Resolution 1.0 Å

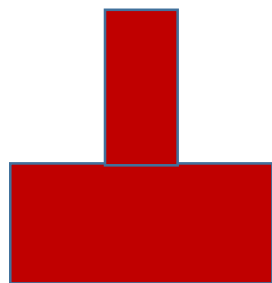


TEM 120 kV
EDS - Cryo
Resolution 3.2 Å

Shared between
soft materials and
life sciences

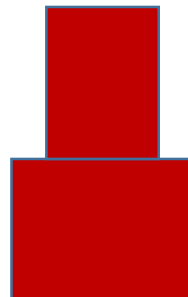


Dual Beam
Dedicated to sample
preparation
Resolution 10 Å



TEM 200-300 kV – Energy
Filter, Phase Plate, Direct
Detector, Resolution ~ 2 Å

~ 2 years



Dual Beam – 3D Reconstruction
Dedicated to Life Sciences
Resolution 10 Å

Currently there are three
corrected instruments in
Brazil, none in São Paulo
state.

Outlook – 3 years

Materials Science



Double Corrected TEM - Holo
STEM, EDS and EELS, In-situ
Tomography, Resolution 1.0 Å



TEM JEOL JEM 2100
STEM, EDS
Resolution 2.4 Å



Dual Beam
Sample Preparation
Resolution 10 Å



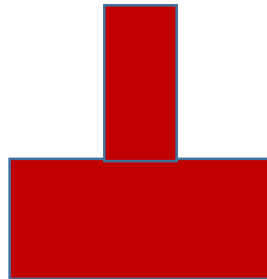
SEM Inspect 50F
STEM and EDS
Resolution 10 Å



SEM Quanta 650F
EDS and EBSD
Resolution 10 Å



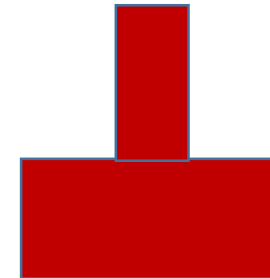
Dual Beam Helios 660
EDS3D and EBSD3D
Nanofabrication
Resolution 6Å



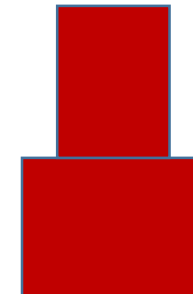
TEM 200-300 kV
Energy Filter, Phase
Plate, Direct Detector,
Resolution ~ 2 Å



TEM JEM 2100F
Phase plate
Resolution 2.4 Å



TEM 120 kV
EDS - Cryo
Resolution 3.2 Å



Dual Beam
3D Reconstruction
Resolution 10 Å

Life Sciences